

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Lee H. Veneklassen

Serial No.: 09/625,284

Filed: July 25, 2000

Title: IMMERSION LENS WITH MAGNETIC
SHIELD FOR CHARGED PARTICLE
BEAM SYSTEM

§ Group Art Unit: 2881
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§ Examiner: D. A. Varfore
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§ Attny Docket No.: 4901

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3/27/03

Date: March 10, 2003

RESPONSE TO RESTRICTION REQUIREMENT UNDER 37 C.F.R. 1.143

Hon. Commissioner of Patents and Trademarks
Washington, D.C. 20231

Sir:

The present communication is in response to the Office Action dated February 11, 2003, outlining the Examiner's restriction requirement between:

I) Claims 1-16 and 29-29, drawn to a charged particle lithography device and method for exposing a substrate, classified in Class 250, subclass 492.1.

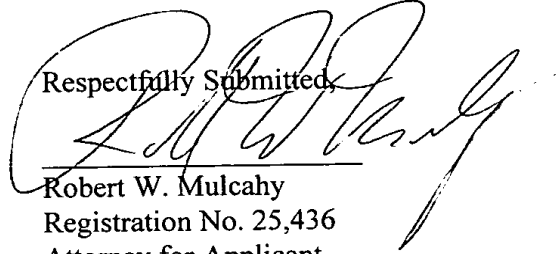
II) Claims 17-24, drawn to a magnetic immersion lens, classified in Class 250, subclass 492.1.

In response to the Examiner's requirement of election of claims, Applicant's undersigned Attorney hereby elects Group II, magnetic immersion lens Claims 17-24, for prosecution, with traverse.

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Applicant's undersigned attorney invites any direct telephone communication from the
~~Examiner to expedite prosecution of the subject Application.~~

Respectfully Submitted,



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